

WHAT IS CLAIMED IS:

1. A color filter substrate for a liquid crystal display comprising:

a substrate;

a black matrix formed on the substrate;

5 a plurality of color filters formed on the substrate with the black matrix, each color filter having a flat central portion, and a peripheral portion placed on the black matrix with a thickness smaller than the central portion; and
a common electrode formed on the plurality of color filters.

10 2. The color filter substrate of claim 1 wherein the neighboring color filters are overlapped with each other over the black matrix.

15 3. The color filter substrate of claim 2 wherein the neighboring color filters are structured such that the peripheral portion of the overlying color filter is overlapped with the peripheral portion of the underlying color filter.

4. The color filter substrate of claim 2 wherein the neighboring color filters are structured such that the peripheral portion of the overlying color filter is overlapped with the peripheral portion of the underlying color filter as well as partially with the central portion of the underlying color filter.

5. The color filter substrate of claim 1 wherein the neighboring color filters are spaced apart from each other with a predetermined distance.

20 6. A method of fabricating a color filter substrate for a liquid crystal display, the method comprising the steps of:

forming a black matrix on a substrate;

sequentially forming a plurality of color filters on the substrate with the black matrix, each color filter having a flat central portion, and a peripheral

portion placed on the black matrix with a thickness smaller than the central portion; and

forming a common electrode on the plurality of color filters.

7. The method of claim 6 wherein the color filters are formed using a mask differentiated in the light transmission while bearing a transparent pattern, an opaque pattern and a semitransparent pattern, the semitransparent pattern of the mask being placed over the peripheral portion of the color filter during the formation of the color filter.

8. A thin film transistor array substrate for a liquid crystal display, the thin film transistor array substrate comprising:

a substrate;

a plurality of gate lines formed on the substrate;

a plurality of data lines crossing over the gate lines while defining pixel regions;

a thin film transistor formed at each pixel region;

a plurality of color filters, each color filter having a flat central portion, and a peripheral portion placed on the data lines with a thickness smaller than the central portion;

a plurality of contact holes exposing the drain electrodes; and

pixel electrodes connected to the drain electrodes through the contact holes.

9. The thin film transistor array substrate of claim 8 wherein the neighboring color filters are overlapped with each other over the data lines.

10. The thin film transistor array substrate of claim 9 wherein the

neighboring color filters are structured such that the peripheral portion of the overlying color filter is overlapped with the peripheral portion of the underlying color filter.

11. The thin film transistor array substrate of claim 10 wherein the neighboring color filters are structured such that the peripheral portion of the overlying color filter is overlapped with the peripheral portion of the underlying color filter as well as partially with the central portion of the underlying color filter.

12. The thin film transistor array substrate of claim 8 wherein the neighboring color filters are spaced apart from each other with a predetermined distance.

13. A method of fabricating a thin film transistor array substrate for a liquid crystal display, the method comprising the steps of:

15. forming a substrate such that the substrate has a plurality of gate lines, a plurality of data lines crossing over the gate lines while defining pixel regions, and thin film transistors provided at the pixel regions while being electrically connected to the gate lines and the data lines;

20 sequentially forming a plurality of color filters, each color filter having a flat central portion, and a peripheral portion placed on the data lines with a thickness smaller than the central portion;

20 forming a plurality of contact holes such that the contact holes expose drain electrodes of the thin film transistors; and

forming a plurality of pixel electrodes connected to the drain electrodes through the contact holes.

14. The method of claim 13 wherein the color filters are formed

using a mask differentiated in the light transmission while bearing a transparent pattern, an opaque pattern and a semitransparent pattern, the semitransparent pattern of the mask being placed over the peripheral portion of the color filter during the formation of the color filter.

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1. A color filter manufacturing method, comprising the steps of:
a) forming a color filter on a substrate, the color filter having a peripheral portion;
b) forming a mask over the peripheral portion of the color filter, the mask having a transparent pattern, an opaque pattern and a semitransparent pattern, the semitransparent pattern of the mask being placed over the peripheral portion of the color filter during the formation of the color filter;
c) forming a gate electrode on the color filter, the gate electrode being formed over the peripheral portion of the color filter; and
d) forming a gate insulating film on the gate electrode, the gate insulating film being formed over the gate electrode.